



# **Semiconductor Memory II**

## **Future Memory Trend**

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2010. 4. 2.

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*VLSI SYSTEM LAB, YONSEI University*  
*School of Electrical & Electronic Engineering*



## **Contents**

**VLSI**  
SYSTEM LAB.

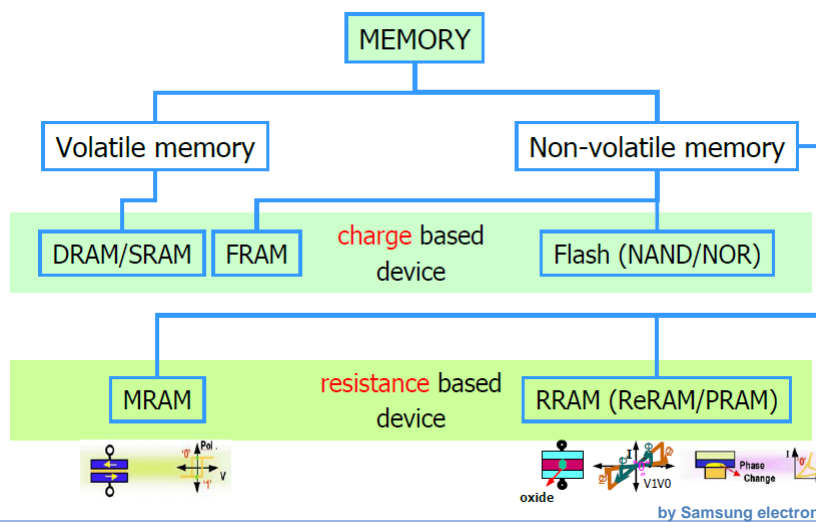
- 1. Future memory trend**
- 2. Future of NAND Flash**
- 3. Universal memory**
  - 1. PRAM**
  - 2. STT-MRAM**

# Future Memory Trend

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SYSTEM LAB.

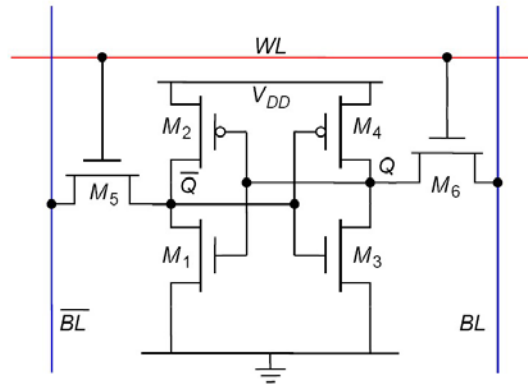
## Memory Hierarchy

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## SRAM Cell

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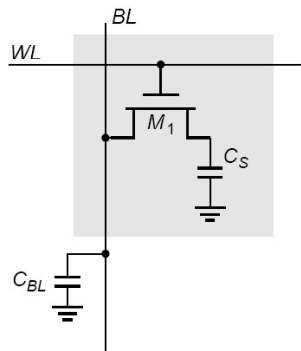


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## DRAM Cell


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SYSTEM LAB.

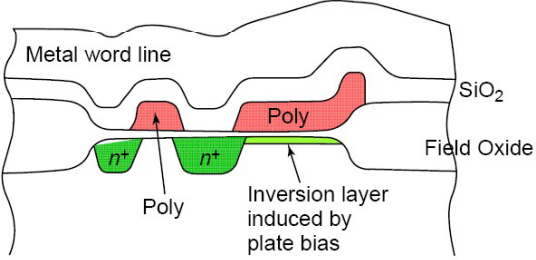


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## DRAM Cell






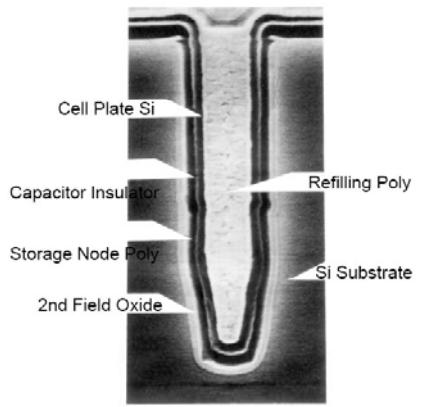
**Cross-section**

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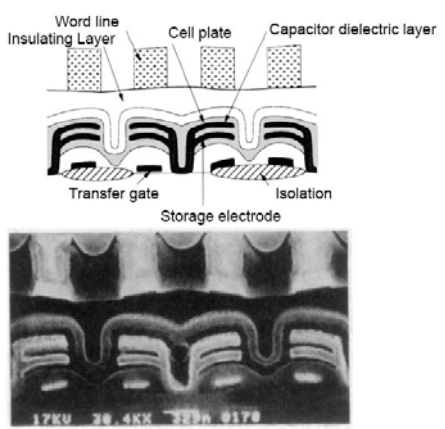


## DRAM Cell






**Trench Cell**




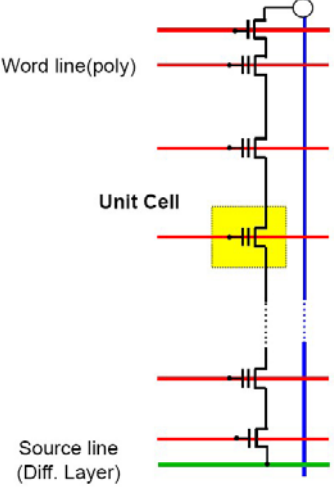
**Stacked-capacitor Cell**

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## Flash Memory Cell

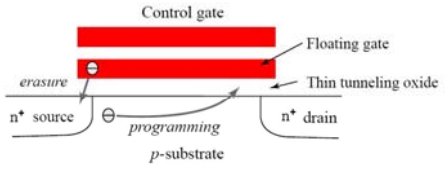




Word line(poly)

Unit Cell

Source line (Diff. Layer)



Control gate

Floating gate

Thin tunneling oxide

n<sup>+</sup> source


n<sup>+</sup> drain

p-substrate


erasure

programming

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## Current Memories Comparison



	DRAM	FLASH	SRAM
Speed	fast	very slow	very fast
Density	high	very high	low
Endurability	better	poor	better
Power	high	very low	low
Refresh	yes	no	no
Retention	volatile	non-volatile	volatile
Scalability	bad	good	good
Data Storage Mechanism	capacitor	FN tunneling, HCI to floating gate	Bi-stable flip-flop

by Korea Institute of Science & Technology Information (KISTI)



## DRAM and SRAM Trend

- ◆ Improve **performance** and capacity of DRAM and SRAM
  - Technology scaling
  - Design technique
- ◆ Function and role of DRAM and SRAM are not changed.
  - SRAM ; cache memory in processor
  - DRAM ; main memory unit in system

Bandwidth vs Year chart showing the evolution of DRAM technologies from SDRAM (1996) to XDR DRAM and NGM diff? (2012). Technologies shown include SDRAM, DDR, DDR2, DDR3, DDR4, XDR DRAM, and NGM diff?.

Contacted Gate Pitch (nm) and SRAM Cell Area ( $\mu\text{m}^2$ ) vs Technology Node. The chart shows that the contacted gate pitch decreases by 0.7x every 2 years, while the SRAM cell area decreases by 0.5x every 2 years. Technology nodes shown are 250nm, 180nm, 130nm, 90nm, 65nm, and 45nm.

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by Intel Technology Journal  
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## NAND Flash Trend

- ◆ Improve **capacity** and performance of NAND flash memory
  - Technology scaling
  - Design technique
- ◆ Positioning of NAND flash have been changed.
  - Past ; digital camera, MP3, USB memory..
  - Recent ; solid state drive (SSD) for replacing HDD

Cell Size ( $\mu\text{m}^2/\text{bit}$ ) vs Start of Mass Production chart for NAND flash. The chart shows a steady decrease in cell size from 64M (1996) to 4bit (2010). Technologies shown include Self-boosting SPPetc., LOCOS, SLC (Single-Level Cell), MLC (Multi-Level Cell), and Super-MLC. Production years shown are '94, '96, '98, '00, '02, '04, '06, '08, '10.

Bit Cost vs Write Speed chart comparing memory technologies. The chart shows that NAND flash has the lowest bit cost and highest endurance (up to  $\sim 10^8$ ), while SRAM has the highest bit cost and lowest endurance ( $\sim 10^{15}$ ). DRAM and NOR are also shown. A red dashed circle highlights the 'Storage Class Memory (SCM)' region, which includes NAND and NOR. Endurance ranges from  $\sim 10^{15}$  for SRAM to  $\sim 10^8$  for NAND.

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by Samsung electronics YONSEI Univ. School of EEE

## Universal Memory

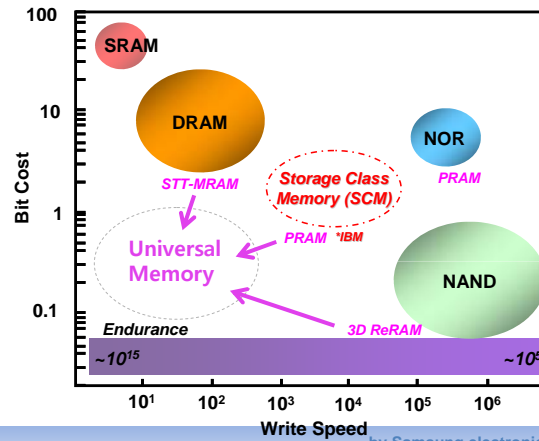
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◆ Universal memory is desired for next-generation memory.

- Nonvolatile memory
- High speed
- High density
- High endurance
- Low power

◆ Some candidates

- PRAM
- STT-MRAM
- FeRAM
- ReRAM
- .....




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## Future of NAND Flash

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# Invention of NAND Flash



Flash Invented      NAND Invented

1967   1971   1979   → 1984   **1987**   1988   1992   1995   1999

**ABSTRACT**


A NAND structure cell is most promising as an ultra high density EEPROM to replace magnetic memories. This paper describes a new device technology to realize a high performance 4Mb EEPROM with NAND structure cell. The main features of the technology are a new NAND structure cell to realize wide threshold window and high reliability, and a high voltage CMOS process to realize program and erase operations, which require high voltage pulses, such as 22V.

By using 1.0um design rules, the unit cell area per bit is 12.9um<sup>2</sup>, which is small enough to realize a 4Mb EEPROM.

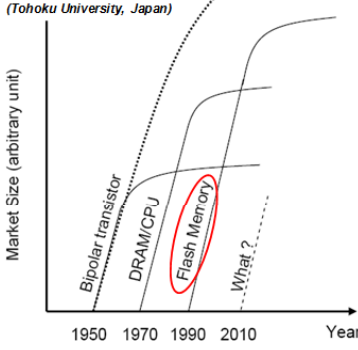
**INTRODUCTION**

In order to replace magnetic memories by solid state devices, a high density EEPROM has been required. Conventional 5V-only EEPROMs, utilizing Fowler-Nordheim tunneling, occupy a very large

by Toshiba, IEDM, 1988




Inventor:  
Prof. F. Masuoka  
(Tohoku University, Japan)




by Toshiba, Flash handbook, 1992


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# Application I / Flash Cards




◆ Flash card is used for mobile devices with memory slot




Digital camera




Portable Video game




PC




Cellular phone





Car navigation

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## Application II / Embedded Application





**8GB Flash**



**MP3 player**







**E-Book**

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## Application III / Contents Preloaded Media






### Software Distribution


→



- Distribute Software as a read-only device
  - > No Viruses
- O/S and Bios already support optical drives
  - > 100% emulation of CD/DVD drive
- Less packaging
- Perfect Application for 3/4bit MLC
- <\$5 unit cost

Santa Clara, CA, USA  
August 2009


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## Application IV / SSD



Samsung 256GB SSD




2.5 inch HDD  
SATA interface



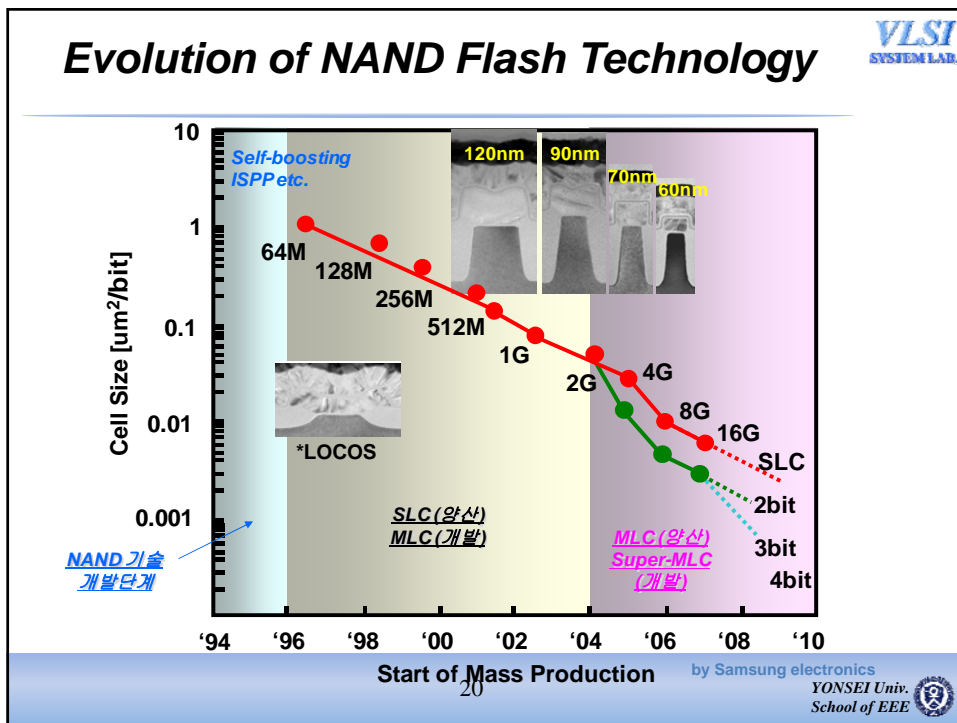
SATA interface

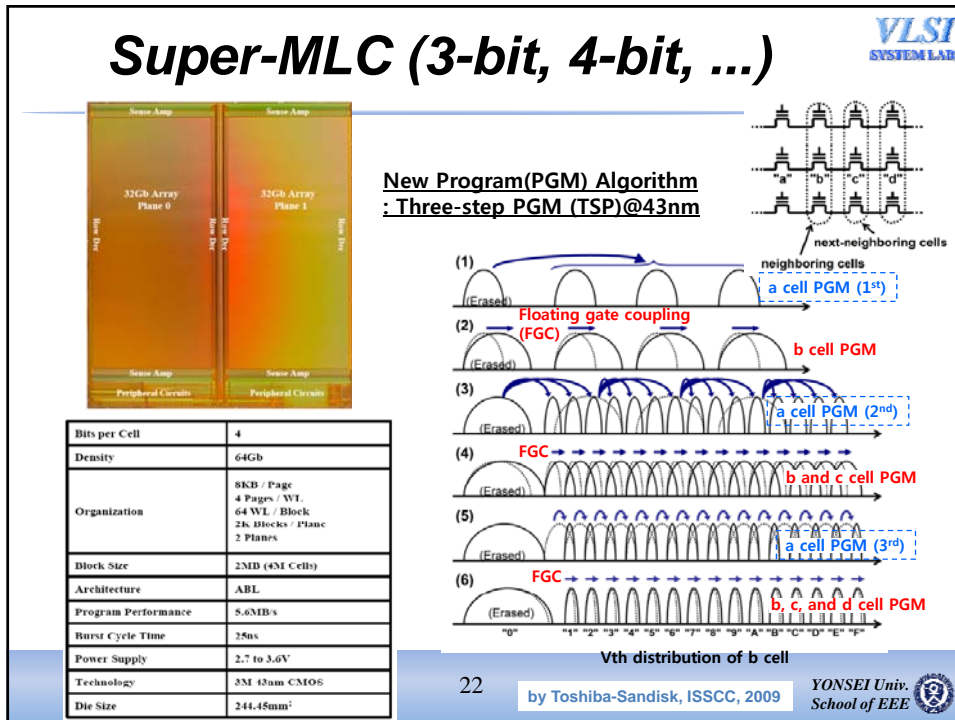
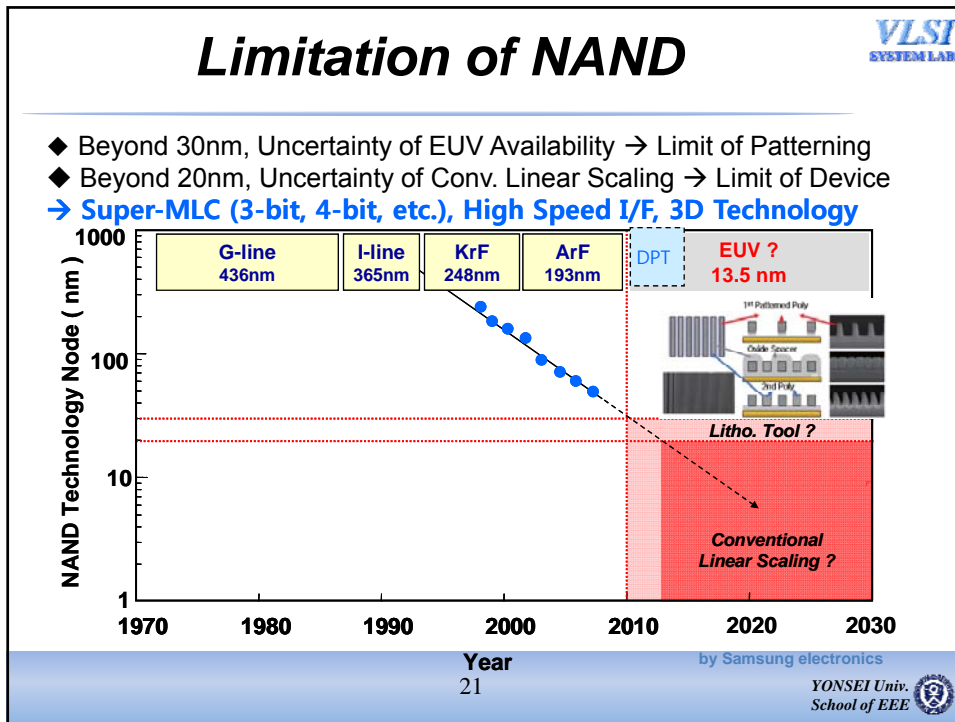
compatibility



SanDisk  
SSD  
SATA 3000 2.5"  
32GB  
2.5 inch SSD

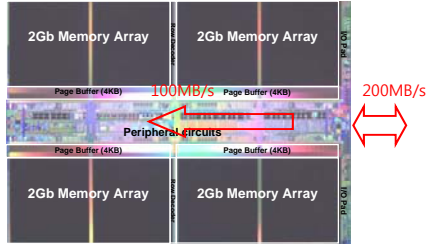
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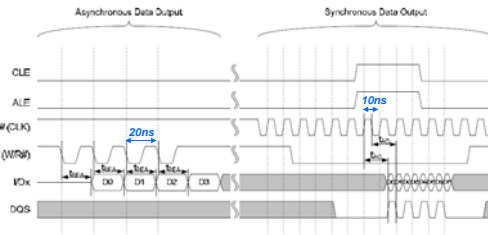
# High Speed Interface (DDR) NAND

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- ONFI (Open NAND Flash Interface)
- : Intel, Micron, Hynix, etc.
- Toggle-mode NAND
- : Samsung, Toshiba

Technology	30nm p-sub CMOS triple-well 3metal
Cell size	0.011 $\mu\text{m}^2$ (effective)
Chip size	169.5mm <sup>2</sup>
Organization	4096 x 128 pages x 312 blocks x 4 planes x 8
Power supply: Vcc	2.7V-3.0V
Power supply: VccQ	1.7V-1.95V or 2.7V-3.5V
Read time	30ns
Program time	160ns (typical)
Erase time	3ms (typical)
Clock cycle time	10ns
I/O width	x8



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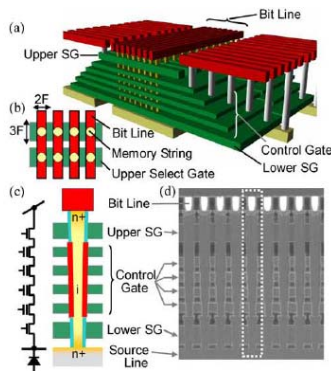
by Micron-Intel, ISSCC, 2008

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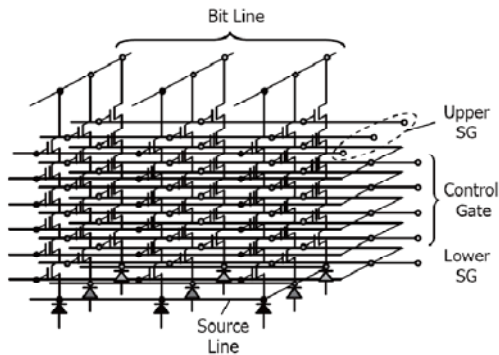
# 3D NAND for Tera-bit Storage

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- ◆ 3D Vertical NAND
- ◆ High Density Oriented, CTF, MLC



by Toshiba, IEDM, 2007





by Toshiba, VLSI, 2007

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## SDD vs. HDD





**2.5" SATA 3.0Gbps SSD**



**2.5" SATA 3.0Gbps HDD**


2.5" SATA 3.0Gbps SSD	Mechanism type	2.5" SATA 3.0Gbps HDD
Solid NAND flash based	Mechanism type	Magnetic rotating platters
64GB	Density	80GB
73g	Weight	365g
Read: 100MB/s, Write :80MB/s	Performance	Read: 59MB/s, Write: 60MB/s
1W	Active Power consumption	3.86W
20G (10~2000Hz)	Operating Vibration	0.5G (22~350Hz)
1,500G for 0.5ms	Shock resistance	170G for 0.5ms
0°C to 70°C	Operating temperature	5°C to 55°C
None	Acoustic Noise	0.3 dB
MTBF >2M hours	Endurance	MTBF < 0.7M hours

**Low weight**  
**High performance**  
**Low power**  
**Low vibration**


**Low noise**  
**Low endurance**

However, high cost per capacity, now

by Samsung electronics

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## Component of SSD



◆ Performance = f(CPU, DRAM, Flash, Host Interface, HW automation)

**DRAM**

- 32 → 128 → 1024 MB
- Mobile SDRAM → DDR → DDR2
- PRAM / FRAM (Future)

**Host Interface**

- PATA → SATA 3G → **SATA 6G** (Note PC)
- SAS 3G → **SAS 6G** (Server / Storage)

**Power Supply**

- Power-Failure Monitor
- Super Cap

**Controller**

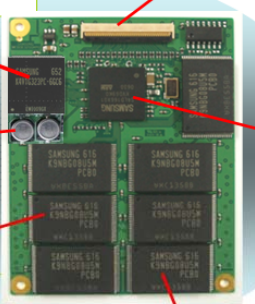
- ARM CPU (133 → 300 MHz)
- Single / Duo Core CPU
- Hardware Acceleration
- 4 / 8 / 16 ch. (NAND I/F)

**NAND Flash**

- SLC/MLC (50 → 40 → 30 nm)
- SDR I/F (40 MB/s/chip)
- DDR I/F (133 → 266, → ... MB/s)

**Firmware**


- w/o OS → Real Time OS
- w/o Queue → Queued CMD

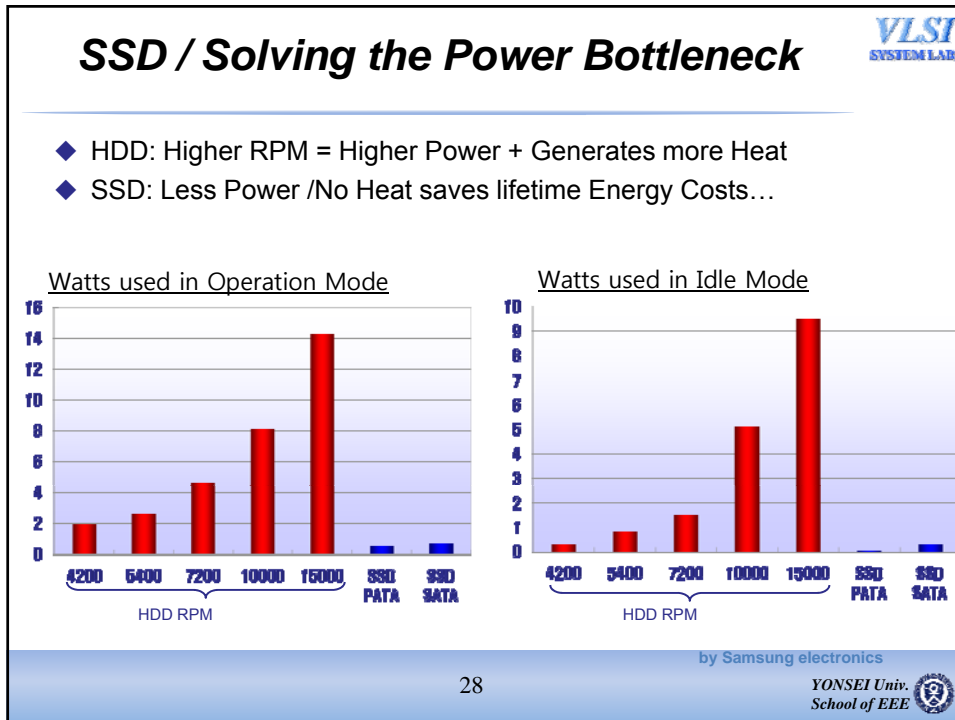
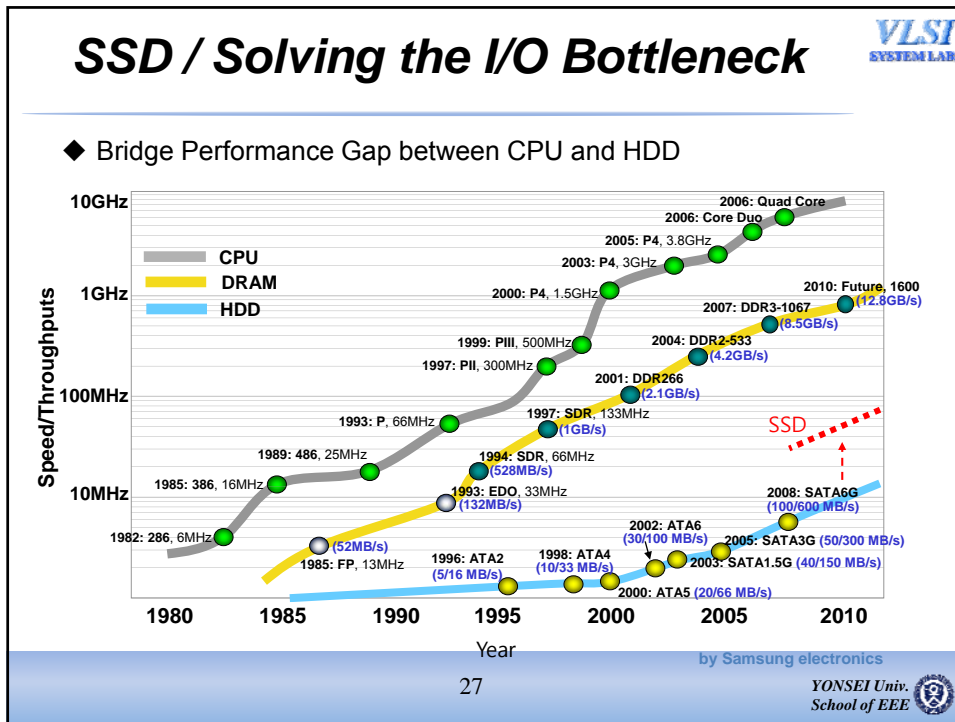


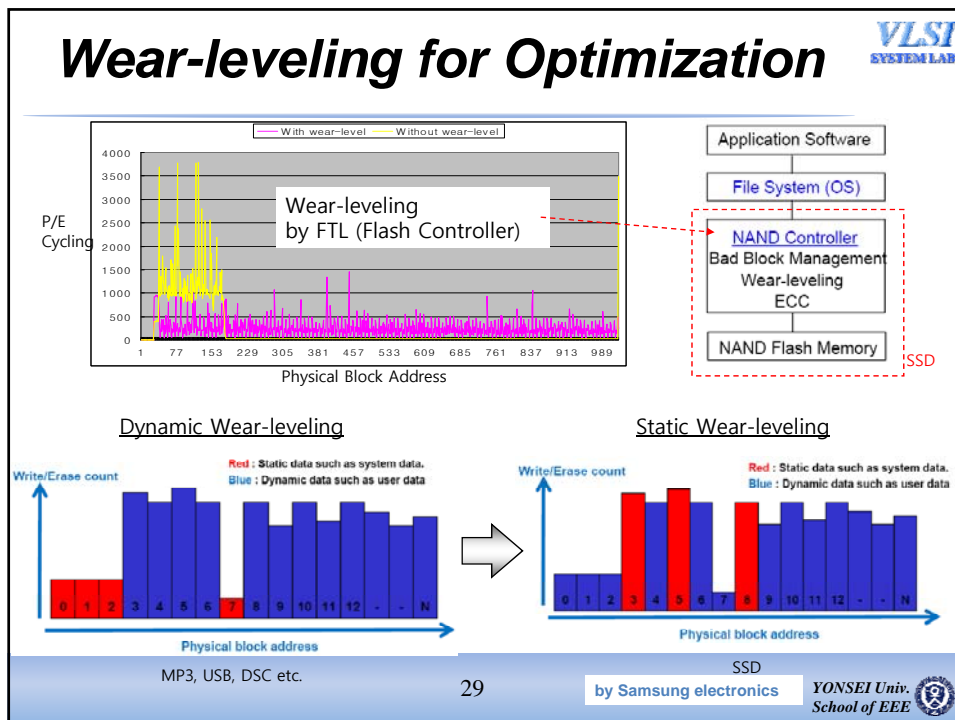
**SSD Capacity**

- 32 / 64 / 128 / 256 / 512 GB

by Samsung electronics

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## Sector Size for Optimization

◆ Existing OS is for HDD! → OS should be optimized for SSD!!!

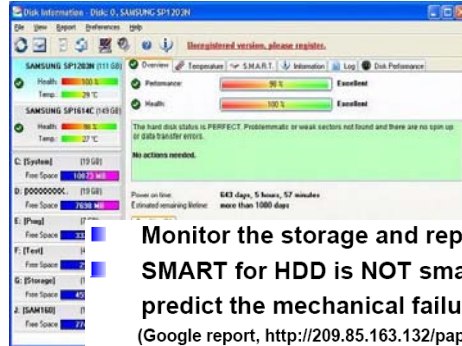
- **Sector size optimization**
  - Minimum write/read unit of NAND is a **page**.
  - Typical page size is 4-8KByte.
  - A page is written only **ONCE** to avoid the program disturbance.
  - With current OS having 512Byte sector, one sector write wastes >80% of data in a page.

- **LBD(Long Block Data)** sector standard (Windows Vista) : 4KByte sector size fits better with SSD.
- **As the page size increases as NAND is shrinking, larger sector size such as 64KByte or 128KByte is required.**

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by K. Takeuchi, ISSCC Forum, 2008
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## Self-monitoring, Analysis and Reporting Technology

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✓ SMART  
(Self-Monitoring, Analysis and Reporting Technology)

Monitor the storage and report/predict the failure.

SMART for HDD is NOT smart because it is very difficult to predict the mechanical failure.

(Google report, [http://209.85.163.132/papers/disk\\_failures.pdf](http://209.85.163.132/papers/disk_failures.pdf))

- SMART for SSD can be really smart.
- Product lifetime can be predicted because the failure rate is highly correlated with the write/erase cycles.
- Predict the SSD lifetime by monitoring the write/erase cycles and replace SSD before the fatal failure occurs.

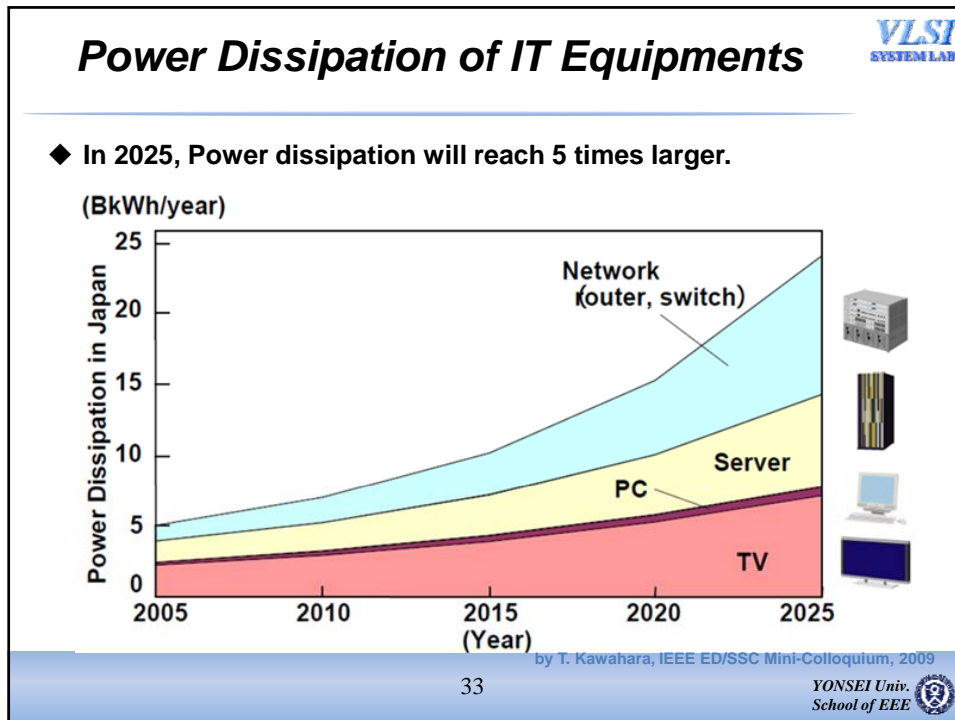
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by K. Takeuchi, ISSCC Forum, 2008

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# Universal Memory

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## Normally OFF, Instant ON

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- ◆ Read operation ; sensing resistance of GST
- ◆ Voltage biased to GST must be limited under  $V_{th}$  to prevent disturb.
- ◆ Current sensing scheme
  - Applying read voltage to cell converts from resistance to current
  - Load device converts from current to voltage
  - Sense amplifier converts from analog voltage value to digital output

by T. Kawahara, IEEE ED/SSC Mini-Colloquium, 2009

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## Change Memory Configuration VLSI SYSTEM LAB.

- ◆ Nonvolatile RAM enhances user's convenience.
- ◆ Instant ON. Quickly software changing.

Memory configuration

w/o UM (conventional)      w/ NVR

Common Data Bus

Copy codes

ROM

RAM

Non-volatile RAM

SPRAM

Normally OFF

Instant ON

by T. Kawahara, IEEE ED/SSC Mini-Colloquium, 2009

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## Nonvolatile (NV) RAM Application VLSI SYSTEM LAB.

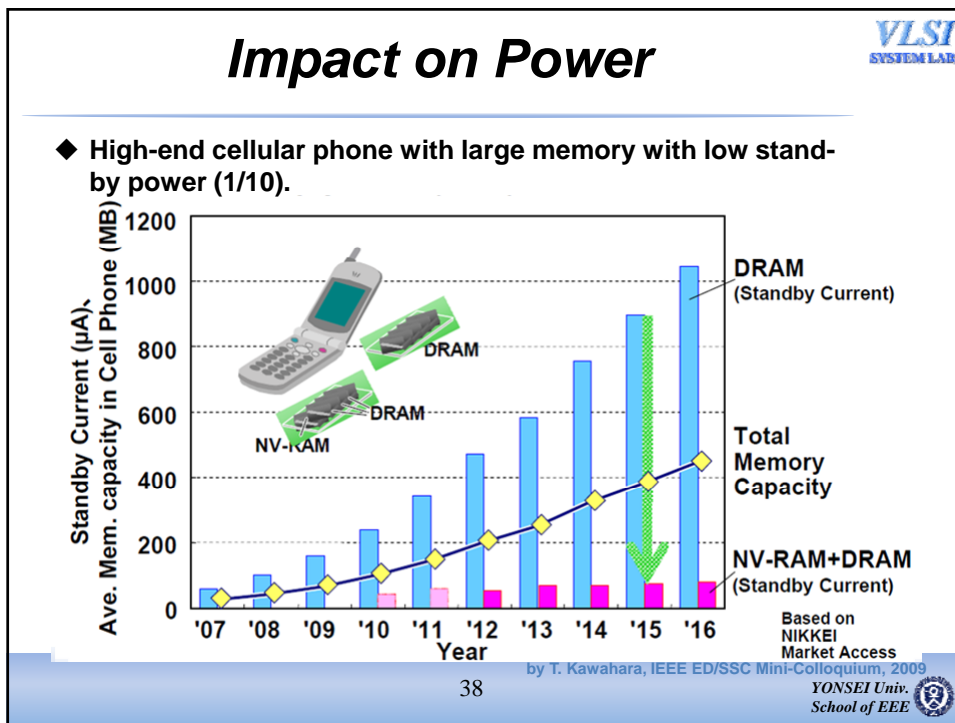
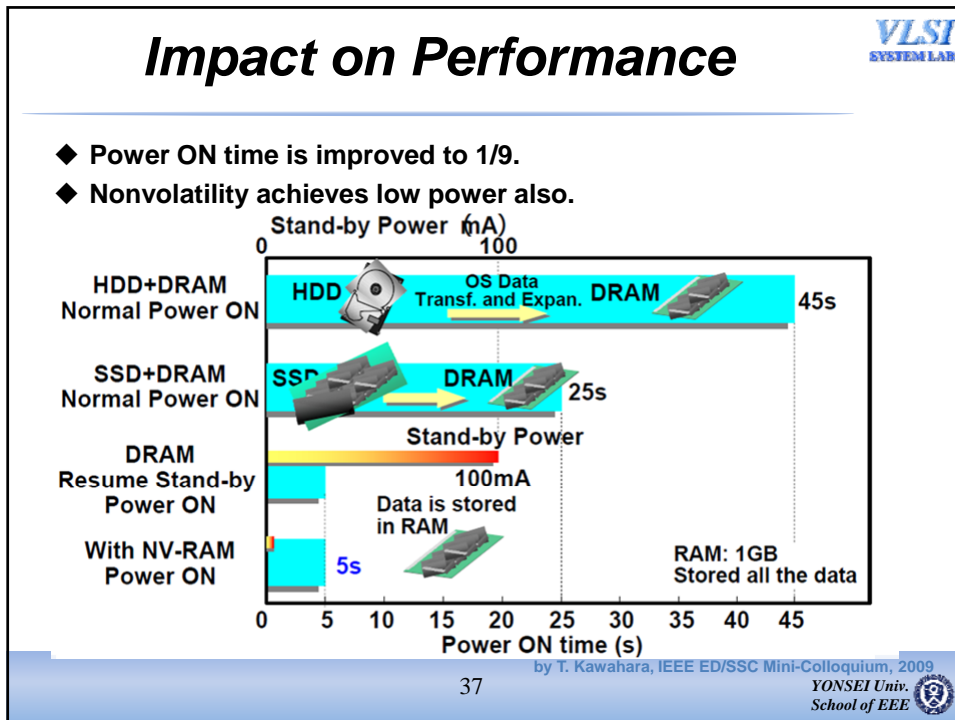
- ◆ Innovation for low power system including hardware, software, and architecture

	Volatile architecture (Now)	Non-volatile architecture	Effect
OS Middle	Layered mem control	NV Arch. control	Reduce power consumption with new power operation
CPU	Volatile logic	Non-volatile logic	Reduce power for FF and registers
Cache	SRAM	Non-volatile RAM + HDD/Flash	Reduce transmission power loss
Working memory	DRAM		Reduce static power for standby mode
Program memory	NOR		
Storage	HDD/Flash		

by T. Kawahara, IEEE ED/SSC Mini-Colloquium, 2009

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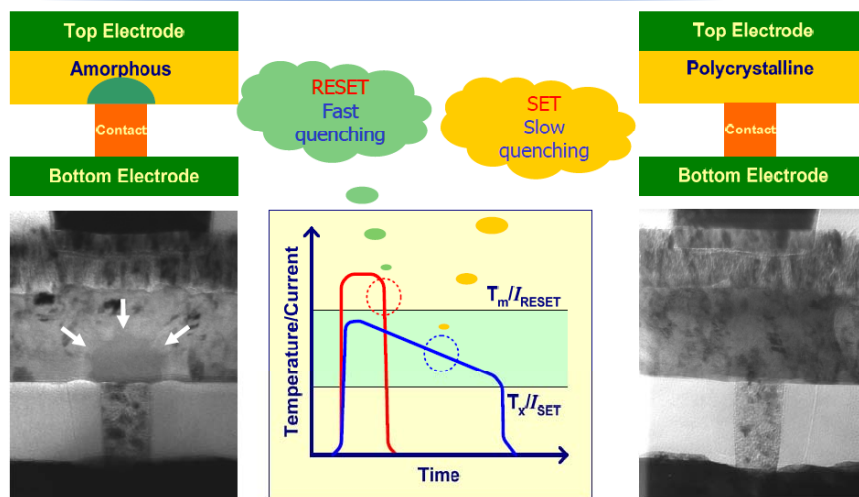


# Universal Memory I PRAM

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## Structure of PRAM Cell

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SYSTEM LAB.



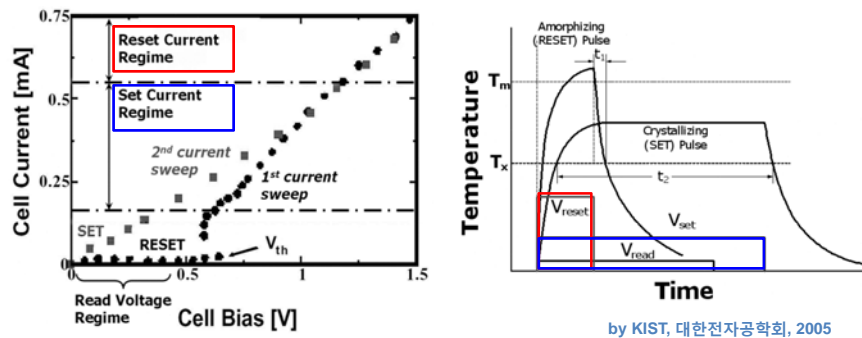
RESET state = High resistance

SET state = Low resistance

## Write Operation of PRAM

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SYSTEM LAB.

- ◆ **Reset pulse** (strong & short) ; Amorphous state ( $\sim 100\text{k}\Omega$ )
- ◆ **Set pulse** (weak & long) ; Crystalline state ( $\text{k}\Omega$ )



by KIST, 대한전자공학회, 2005

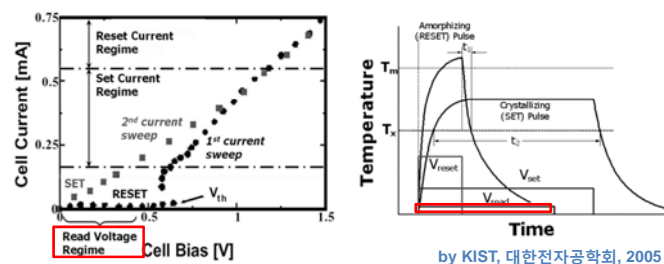
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## Read Operation of PRAM

VLSI  
SYSTEM LAB.

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- ◆ Voltage biased to GST must be limited under  $V_{th}$  to prevent disturb.
- ◆ Current sensing scheme
  - Applying read voltage to cell converts from resistance to current
  - Load device converts from current to voltage
  - Sense amplifier converts from analog voltage value to digital output



by KIST, 대한전자공학회, 2005

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## Recent Technical Issues

### Reducing Required RESET Current

◆ Reducing BEC

Increasing heat by increasing current density  
→ reducing  $I_{RESET}$

◆ Confined contact

Increasing heat by increasing current density  
→ reducing  $I_{RESET}$

by Samsung Electronics, Sym. VLSI Tech., 2007

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## Recent Technical Issues

### Reducing Required RESET Current

◆ Impurity doping

Increasing GST resistance  
→ increasing heat  
→ reducing  $I_{RESET}$

Reset Current Regime

by Samsung Electronics, Sym. VLSI Tech., 2007

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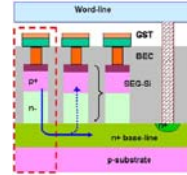
## Recent Technical Issues

### Obtaining Larger RESET Current

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#### ◆ Enhancing current driving capability

- Vertical BJT



	256 Mb PRAM Cell ISSCC2006	512Mb PRAM Cell ISSCC2007
Unit Cell Structure		
Switch Device	(3-terminal) MOS Switch	(2-terminal) Diode Switch
Process Tech.	100nm	90nm
Cell Size	0.166mm <sup>2</sup> (16.6F <sup>2</sup> )	0.0467mm <sup>2</sup> (5.8F <sup>2</sup> )
Switch Device Capability	6 mA/mm <sup>2</sup> @ V <sub>ds</sub> =1.5V, V <sub>gs</sub> =3.0V	21mA/mm <sup>2</sup> @ V <sub>diode</sub> =1.5V
Integration Density (Chip Size)	256 Mb (79.2 mm <sup>2</sup> )	512Mb (91.5 mm <sup>2</sup> )

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## History of PRAM

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- **2000**
  - STMicroelectronics obtained license about CD-ROM from Ovonyx and started researching with Ovonyx to develop PRAM.
- **2002**
  - Intel and Ovonyx are developed 4Mb PRAM
- **2004**
  - STMicroelectronics developed 8Mb PRAM using 0.18um tech.
  - Samsung developed 64Mb PRAM using 0.18um tech.
- **2005**
  - Samsung developed 256Mb PRAM.

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## History of PRAM

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- **2007**
  - **Samsung** developed 512Mb PRAM using 90nm tech. (using N-doped GST, vertical BJT)
  - **Hynix** obtained license about PRAM from Ovonyx.
  - **Numonyx** developed 128Mb PRAM.
- **2008**
  - **Numonyx** developed 128Mb PRAM with multi level cell(MLC).
- **2010**
  - **Numonyx** developed 1Gb PRAM.

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## Future of PRAM

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- ◆ When ?? 2010 ?
  - **Samsung** and **Numonyx** expect to possess technology to mass-produce 512Mb~1Gb PRAM.
  - Absence of alternative market is obstacle of commercialization of PRAM.
  - **Samsung** or **Numonyx** may launch PRAM in 2010.
- ◆ Target !! NOR Flash !!
  - Recently, improvement of NOR flash disturbs commercialization of PRAM.
  - Main product of NOR flash is 256, 512Mb and uses for embedded system.
- ◆ Future !!
  - SSD drive
  - System that don't need booting

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## Universal Memory II

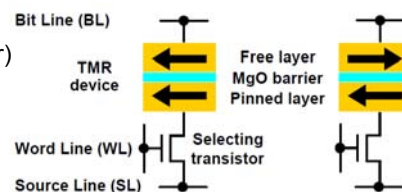
### STT-MRAM

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SYSTEM LAB.

### MTJ Device Structure

VLSI  
SYSTEM LAB.

- ◆ MTJ
  - Two magnetic layer(Free and pinned layer)
  - Insulating layer(Tunnel barrier)



- ◆  $R_{MTJ}$  ; depends on the state of free layer


	State	Effective resistance
Parallel	0	Low ( $R_0$ )
Anti-Parallel	1	High ( $R_1=R_0*(1+MR)$ )

(MR ; magnetoresistance)

Reading operation → Reading resistance of MTJ

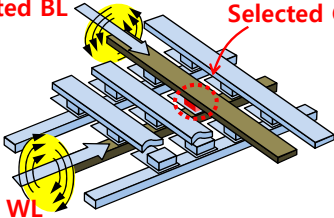
Writing operation → Switching free layer of MTJ

## Write Operation of Conventional MRAM

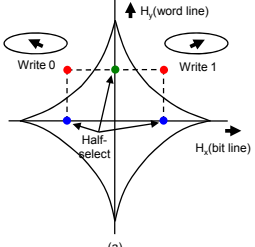


◆ **Applied Magnetic Fields**

**Selected BL**



**Selected Cell**

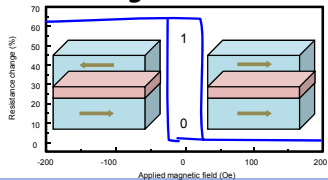


(a)

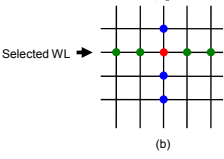
**Selected WL**

< Applied magnetic field >

◆ **State Change**




(b)



(b)


< State change >

T. M. Maffitt, et al., IBM J., 2007

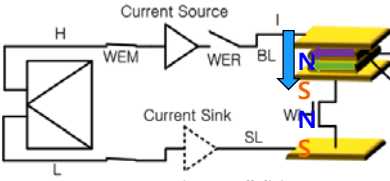


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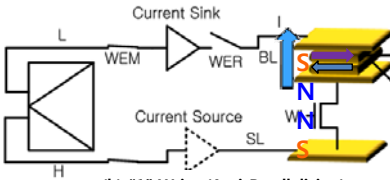
## Write Operation of STT-MRAM



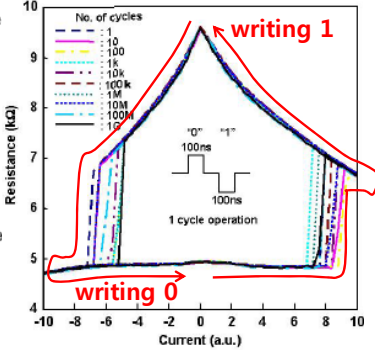
◆ **Spin-polarized electron**



(a) "0" Write (Parallelizing)




(b) "1" Write (Anti-Parallelizing)



(c) R-I Characteristics

< Parallelizing and Anti-Parallelizing Current >

by T. Kawahara, et al., ISSCC, 2007



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## Conventional MRAM vs. STT-MRAM

◆ STT-MRAM has good potential in scalability due to Write current.

Conventional MRAM

STT-MRAM

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by Samsung electronics  
 YONSEI Univ. School of EEE

## Recent Technical Issues

### Reducing Required Critical Current

◆ Perpendicular MTJ

- TMR element with perpendicular magnetic anisotropy (P-TMR)
- Lower critical current than I-TMR

Research Group	Conference	MTJ size (diameter)	Critical current	Switching time
Toshiba	IEDM2008	55nm	49uA (AP-P) 100uA (P-AP)	4ns

$I_c = 49\mu A$

Critical current ( $I_c$ ) of P-ST is dependent on MTJ size. (opposite result compared with page 2)

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by T. Kishi, et al., IEDM, 2008  
 YONSEI Univ. School of EEE

## Recent Technical Issues

### Obtaining Larger Write Current

VLSI SYSTEM LAB.

#### ◆ 2 Transistor – 1 MTJ (2T1MTJ) cell structure

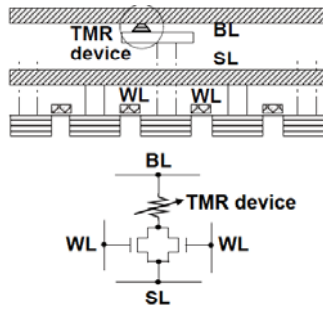


Fig. 1 2T1R Memory Cell

To minimize the cell area, the isolation area between a cell and an adjacent cell is replaced by the adjacent cell's transistor; the "off" state of the channel region of the adjacent cell can insulate electrically among memory cells.

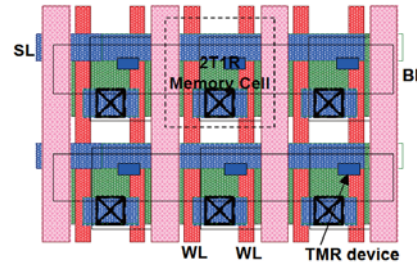


Fig. 2 Cell Layout

Larger write current with same area

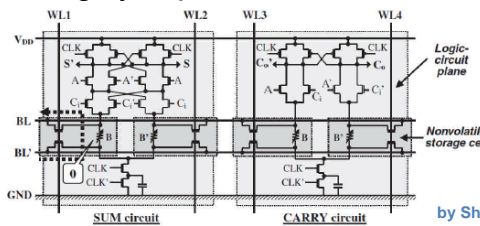
by R. Takemura, et al., Symposium on VLSI circuits, 2009

## NEW Application using MTJ

### Spintronics Logic

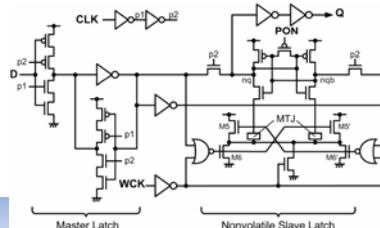
VLSI SYSTEM LAB.

- ◆ Recently, nonvolatile logic using MTJ had been studied.
- ◆ Highly expected for LSI advancement and innovation.



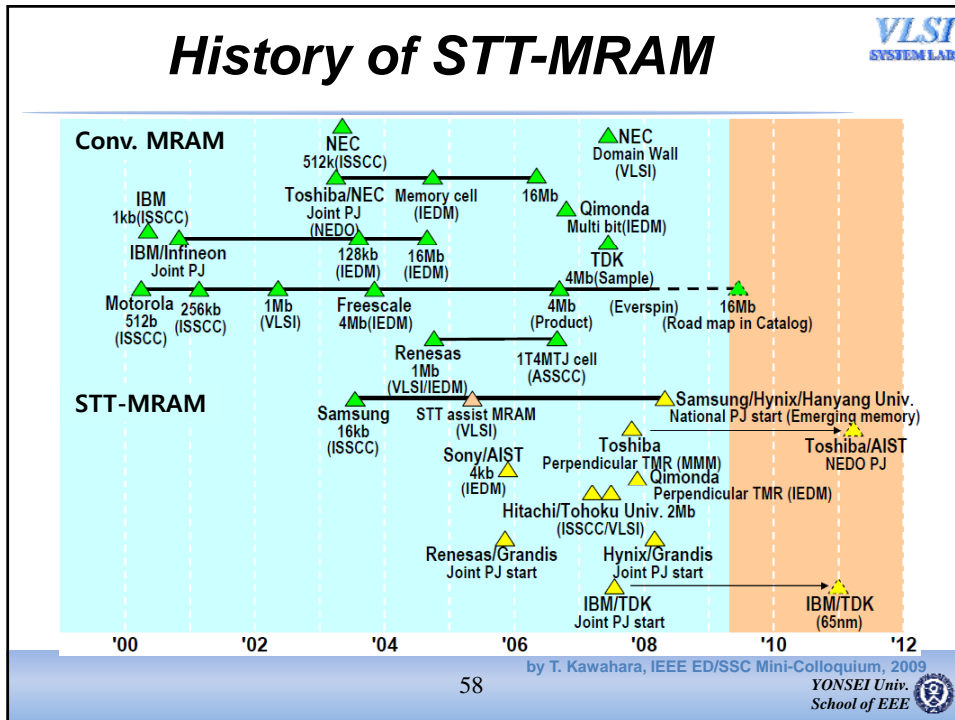
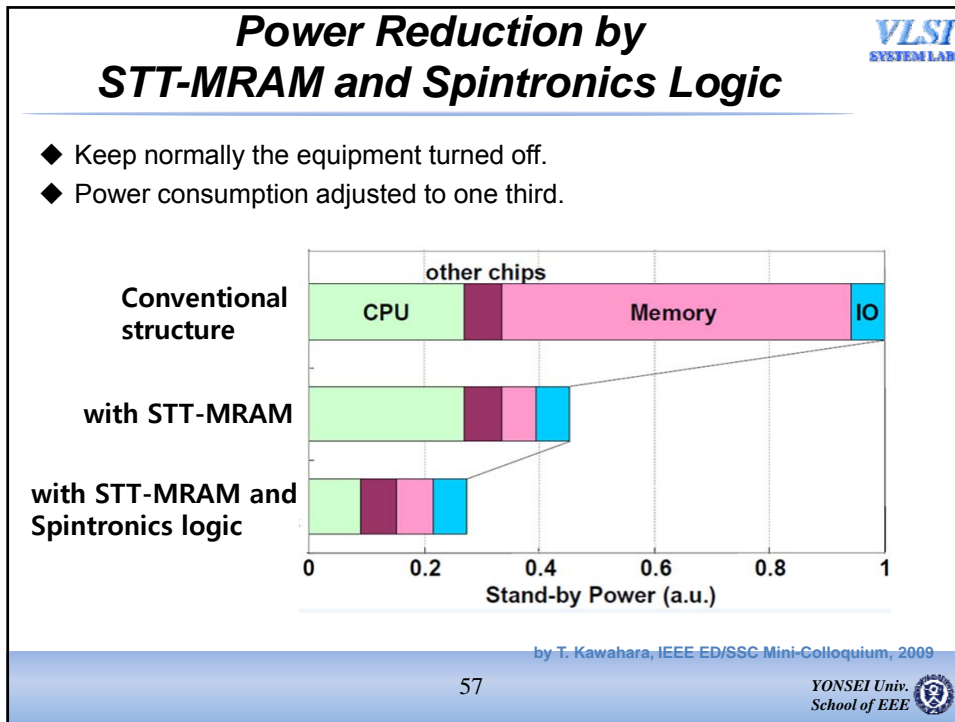
- Full adder with nonvolatile input B**
- Dynamic logic type
  - Dynamic power can reduced to 23%

by Shoun Matsunaga, et al., Applied Physics Express, 2008



- Nonvolatile Flip-flop**
- Cross-coupled inverter latch type
  - Standby power can reduced to 0%

by Noboru Sakimura, et al., CICC, 2008



## Conclusion

VLSI  
SYSTEM LAB.

- ◆ The density and performance of flash memory have been improved by improvement of process and design technology.
- ◆ Solid state drive (SSD) is remarkable as alternate storage device. As cost per capacity decreases, SSD will replace HDD, gradually.
- ◆ Advantage of SSD
  - Low power
  - High performance
  - No noise & vibration
  - Low heat
- ◆ Next generation memory had been studied for overcoming current memory. (PRAM, STT-MRAM, ...)
- ◆ Requirement for universal memory
  - Nonvolatile
  - Low power
  - High performance
  - High density